IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. *(Previously Presented):* A lithographic support system, comprising:

a moveable support structure configured to support and move an object, said support structure comprising a robot arm having a rod coupled to a support frame that is provided with a clamp that clamps the object; and

a compliant structure configured to compensate for at least one of a tilt and displacement between said object and said clamp, the compliant structure being provided at least between the rod and the support frame.

2. *(Cancelled):*

3. *(Previously Presented):* The lithographic support system of Claim 1, wherein said compliant structure comprises two or more compliant rods that are rotatable at their ends.

4. *(Previously Presented):* The lithographic support system of Claim 1, wherein said compliant structure comprises a notch such that a front portion of the support frame is enabled to rotate.

5. *(Previously Presented):* The lithographic support system of Claim 1, further comprising a second compliant structure provided on said clamp.

6. *(Previously Presented):* The lithographic support system of Claim 1, wherein said support frame is in a plane defined by a x-axis, a y-axis, and a z-axis being perpendicular to said x-axis and said y-axis, said compliant structure providing a compliance in at least one of a first rotation (Rx) about said x-axis, a second rotation (Ry) about said y-axis, and a z-direction parallel to said z-axis.

7. *(Original):* The lithographic support system of Claim 3, wherein said compliant structure is arranged such that said support frame is allowed to rotate about a predetermined center of rotation.

8. *(Original):* The lithographic support system of Claim 1, wherein said object comprises a substrate (W).

9. *(Cancelled).*

10. *(Original):* The lithographic support system of Claim 1, wherein said compliant structure comprises a metal flexure.

11.-14. *(Cancelled)*

15. *(Previously Presented)* A lithographic robot, comprising:

a robotic arm configured to hold and move an object, the robotic arm having a rod coupled to a support frame that is provided with a clamp; and

a compliant structure configured to compensate for at least one of a tilt and displacement between said object and said robotic arm, the compliant structure being provided at least between the rod and the support frame.

16. *(Previously Presented):* The lithographic robot of Claim 15, wherein said compliant structure comprises two or more compliant rods that are rotatable at their ends.

17. *(Previously Presented):* The lithographic robot of Claim 16, wherein said compliant structure comprises a notch such that a front portion of the support frame is enabled to rotate.

18. *(Previously Presented):* A lithographic apparatus, comprising:

a radiation system configured to provide a beam of radiation;

a support structure configured to support a patterning device that imparts a desired pattern onto said beam of radiation;

a substrate holder configured to hold a substrate;

a projection system configured to project said patterned beam onto a target portion of said substrate; and

a support system that holds and moves one of said substrate, said patterning device, and an object, in which said support system comprises:

a support frame provided with a clamp;

a rod coupled to the support frame; and

a compliant structure configured to compensate for at least one of a tilt and displacement between said substrate, said patterning device, or said object and said clamp, the compliant structure being provided at least between the rod and the support frame.

19.-20. *(Cancelled)*

21. *(Previously Presented)*: A device manufacturing method, comprising:

providing a substrate via a support system, said supporting system comprising a rod coupled to a support frame that is provided with a clamp structure that clamps said substrate, said supporting system configured to hold and move said substrate and compensate for at least one of a tilt and displacement between said substrate and said clamping structure by employing a compliant structure provided at least between the rod and the support frame;

providing a beam of radiation using a radiation system;

imparting a desired pattern onto said beam of radiation by a patterning device; and

projecting said patterned beam of radiation onto a target portion of said substrate via a projection system.

22. *(Cancelled)*.

23. *(Previously Presented)* The lithographic support system of Claim 1, wherein the clamp is in contact with the object.

24. *(Previously Presented)* The lithographic support system of Claim 1, wherein the compliant structure is arranged at least between the rod and the support frame so as to be in a contactless relationship with the object.

25.   (*Previously Presented*) The lithographic support system of Claim 1, wherein the compliant structure is configured to compensate for at least one of a tilt and displacement between the object and the clamp during transport of the object between a first and a second support, the first and the second support configured to support the object.

26.   (*Previously Presented*) A lithographic support system, comprising:

a moveable support structure configured to support and move an object, the support structure comprising a robot arm having a rod coupled to a support frame that includes a clamp configured to clamp the object; and

a compliant structure configured to compensate for at least one of a tilt and displacement between the object and the clamp during transport of the object between a first and a second support, the first and the second support configured to support the object, the compliant structure provided on the rod or the support frame so as to be in a contactless relationship with the object.

27.   (*Previously Presented*) The lithographic support system of Claim 26, wherein the clamp is in contact with the object.